



US00D789311S

(12) **United States Design Patent**
Okada et al.

(10) **Patent No.:** **US D789,311 S**
(45) **Date of Patent:** **** Jun. 13, 2017**

(54) **PATTERN WAFER**

(71) Applicants: **Hitachi Kokusai Electric Inc.**, Tokyo (JP); **Techno Quartz Inc.**, Tokyo (JP)

(72) Inventors: **Hiromi Okada**, Toyama (JP); **Masayuki Yamada**, Toyama (JP); **Satoshi Aizawa**, Toyama (JP); **Shinya Morita**, Toyama (JP); **Masayoshi Minami**, Toyama (JP); **Kazuhisa Osaka**, Tokyo (JP)

(73) Assignees: **HITACHI KOKUSAI ELECTRIC INC.**, Tokyo (JP); **TECHNO QUARTZ INC.**, Tokyo (JP)

(**) Term: **15 Years**

(21) Appl. No.: **29/569,274**

(22) Filed: **Jun. 24, 2016**

(30) **Foreign Application Priority Data**

Dec. 28, 2015 (JP) 2015-029187

(51) **LOC (10) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/182**

(58) **Field of Classification Search**

USPC D13/182; D6/309

CPC C30B 25/02; C30B 25/04; C30B 25/12; C30B 25/18; C30B 25/186; C30B 25/20;

H01L 21/2018; H01L 21/2003; H01L 21/02367; H01L 21/0237; H01L 21/02428; H01L 21/0243; H01L 21/02433; H01L 21/02436; H01L 21/31116; H01L 21/32139; H01L 21/31114; H01L 21/0337; H01L 21/31138; H01L 21/02439; H01L 21/3213; H01L 21/32131; H01L 21/32133; H01L 21/32135; H01L 21/823807; H01L 21/84; H01L 21/31055; H01L 21/31053; H01L 21/76819; H01L

21/31111; H01L 33/16; H01L 29/02; H01L 29/04; H01L 29/045; H01L 29/06; H01L 29/0603; H01L 29/66765; H01L 29/66757; H01L 27/1203; H01L 27/1218; H01L 27/1222; H01S 5/3202

See application file for complete search history.

(56) **References Cited**

U.S. PATENT DOCUMENTS

3,461,537 A * 8/1969 Lotz H01L 21/67132
206/710
4,630,093 A * 12/1986 Yamaguchi H01L 21/02019
148/33
5,182,233 A * 1/1993 Inoue H01L 21/304
148/DIG. 28

(Continued)

Primary Examiner — Elizabeth J Oswecki

(74) *Attorney, Agent, or Firm* — Fitch, Even, Tabin & Flannery, LLP

(57) **CLAIM**

The ornamental design for a pattern wafer, as shown and described.

DESCRIPTION

FIG. 1 is a front elevational view of a pattern wafer, showing our new design;

FIG. 2 is a rear elevational view thereof;

FIG. 3 is a left side elevational view thereof;

FIG. 4 is a right side elevational view thereof;

FIG. 5 is a top plan view thereof;

FIG. 6 is a bottom plan view thereof;

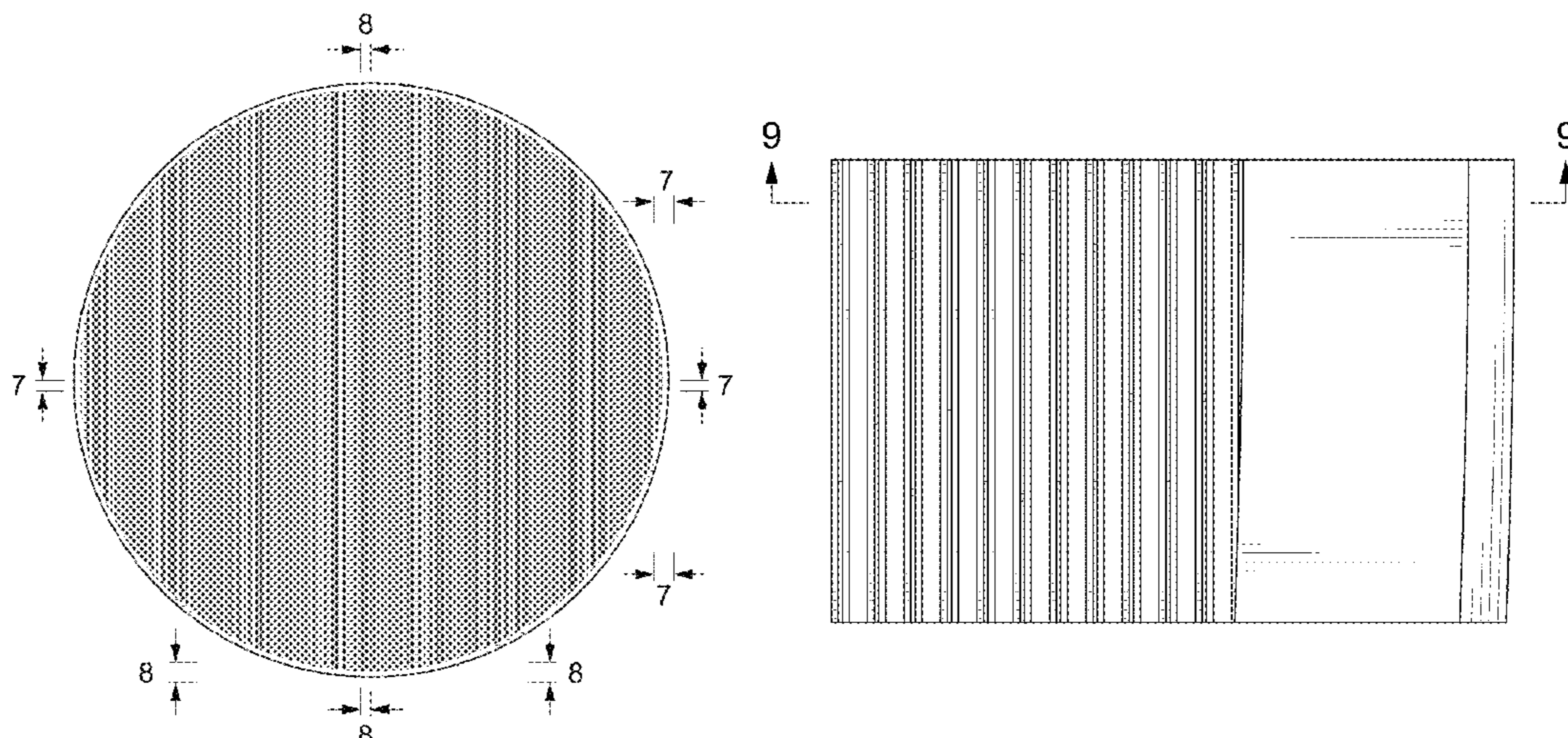
FIG. 7 is an enlarged front portion view taken along line 7-7 in FIG. 1;

FIG. 8 is an enlarged front portion view taken along line 8-8 in FIG. 1;

FIG. 9 is a cross sectional view taken along line 9-9 in FIG. 7; and,

FIG. 10 is a top perspective view of FIG. 8.

1 Claim, 5 Drawing Sheets



(56)

References Cited

U.S. PATENT DOCUMENTS

5,314,844 A *	5/1994	Imamura	B28D 5/0005	8,865,580 B2 *	10/2014	Kobayashi	H01L 21/31144
				148/DIG. 28					438/585
7,115,984 B2 *	10/2006	Poo	H01L 23/49805	D716,742 S *	11/2014	Jang	D13/182
				174/257	8,882,917 B1 *	11/2014	Cheng	C23C 14/54
D552,565 S *	10/2007	Nakamura	D13/182					118/715
7,462,094 B2 *	12/2008	Yoshida	B24B 1/00	D720,313 S *	12/2014	Flynn	D13/182
				451/287	2002/0121915 A1 *	9/2002	Alonso		
D614,593 S *	4/2010	Lee	D13/182			Montull	H01L 21/67288
7,705,430 B2 *	4/2010	Sekiya	H01L 21/78					324/754.03
				257/619	2004/0124413 A1 *	7/2004	Arai	H01L 21/67259
7,871,928 B2 *	1/2011	Chiang	B82Y 30/00					257/48
				438/485	2004/0259332 A1 *	12/2004	Fukuoka	B24B 7/228
D651,991 S *	1/2012	Nishiguchi	D13/182					438/464
D651,992 S *	1/2012	Nishiguchi	D13/182	2005/0170616 A1 *	8/2005	Murata	H01L 21/3043
D655,256 S *	3/2012	Nishiguchi	D13/182					438/463
8,555,492 B2 *	10/2013	Wang	B26D 3/06	2007/0082508 A1 *	4/2007	Chiang	C23C 14/54
				29/846					438/800
					2011/0111593 A1 *	5/2011	Kanno	B82Y 10/00
									438/689

* cited by examiner

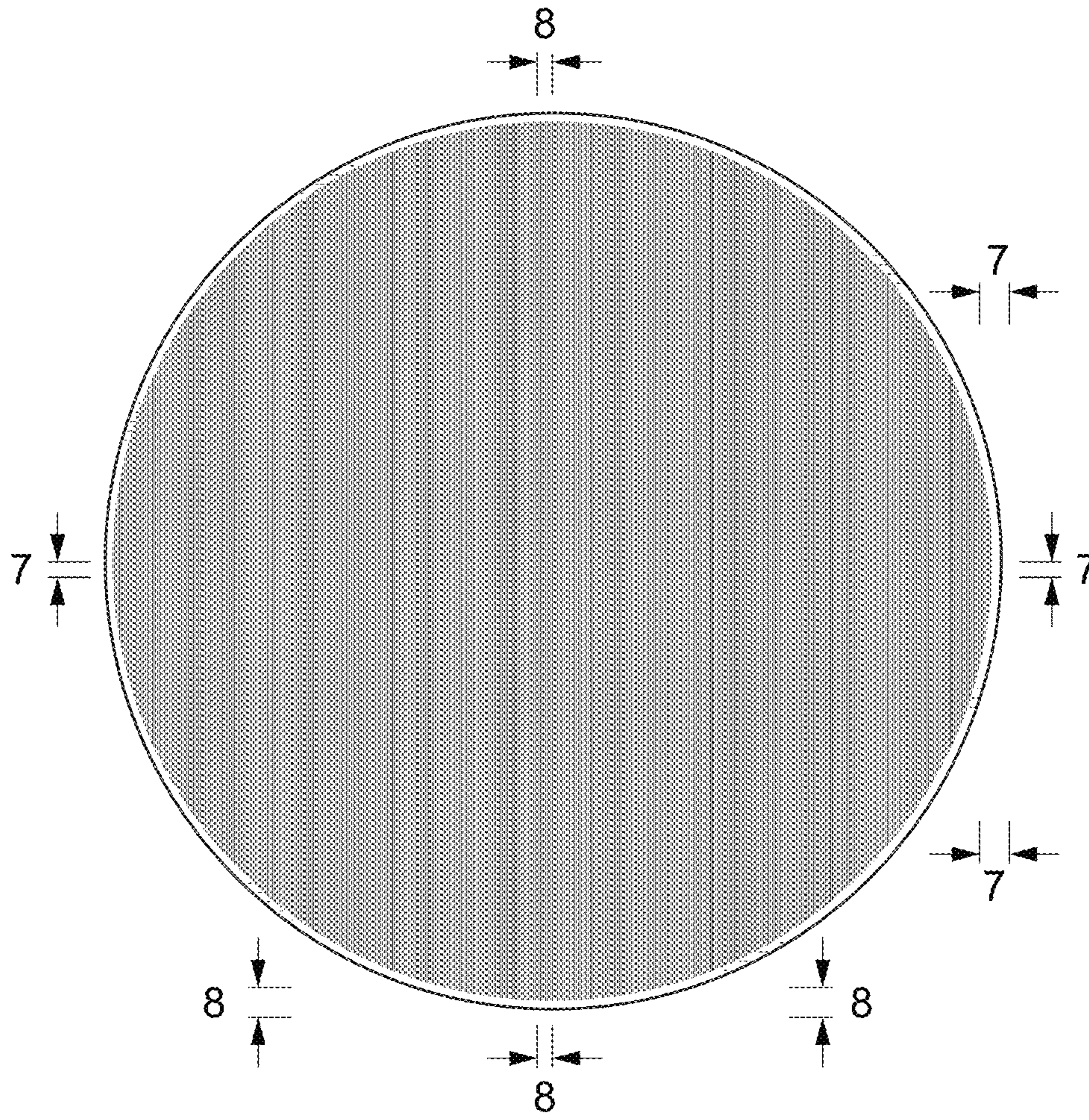


FIG. 1

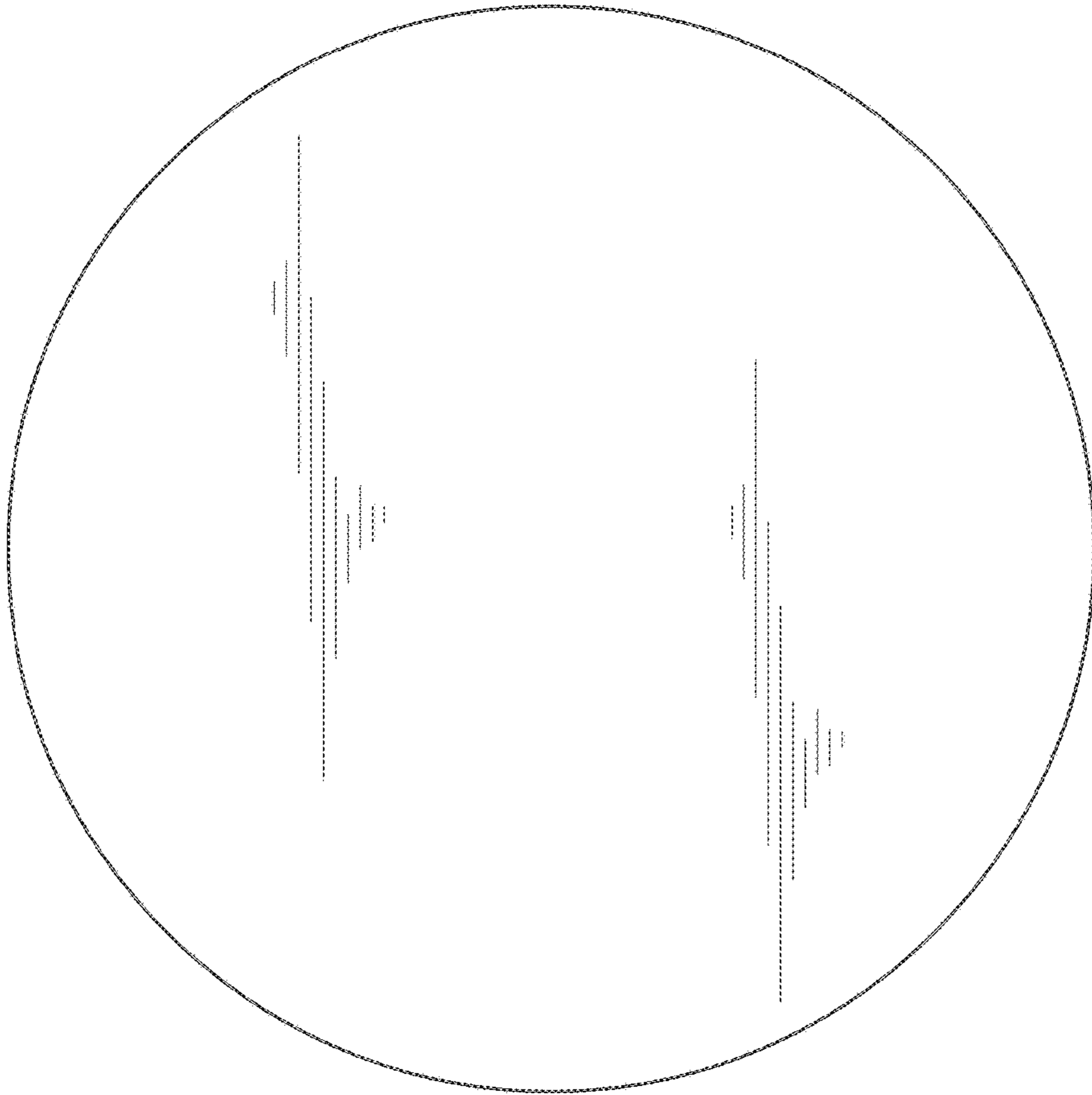


FIG. 2



FIG. 3

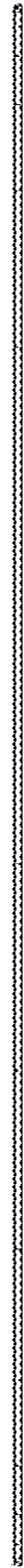


FIG. 4

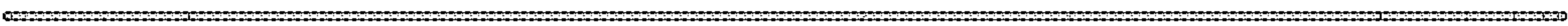


FIG. 5

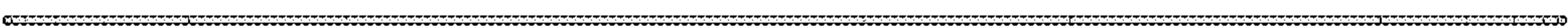


FIG. 6

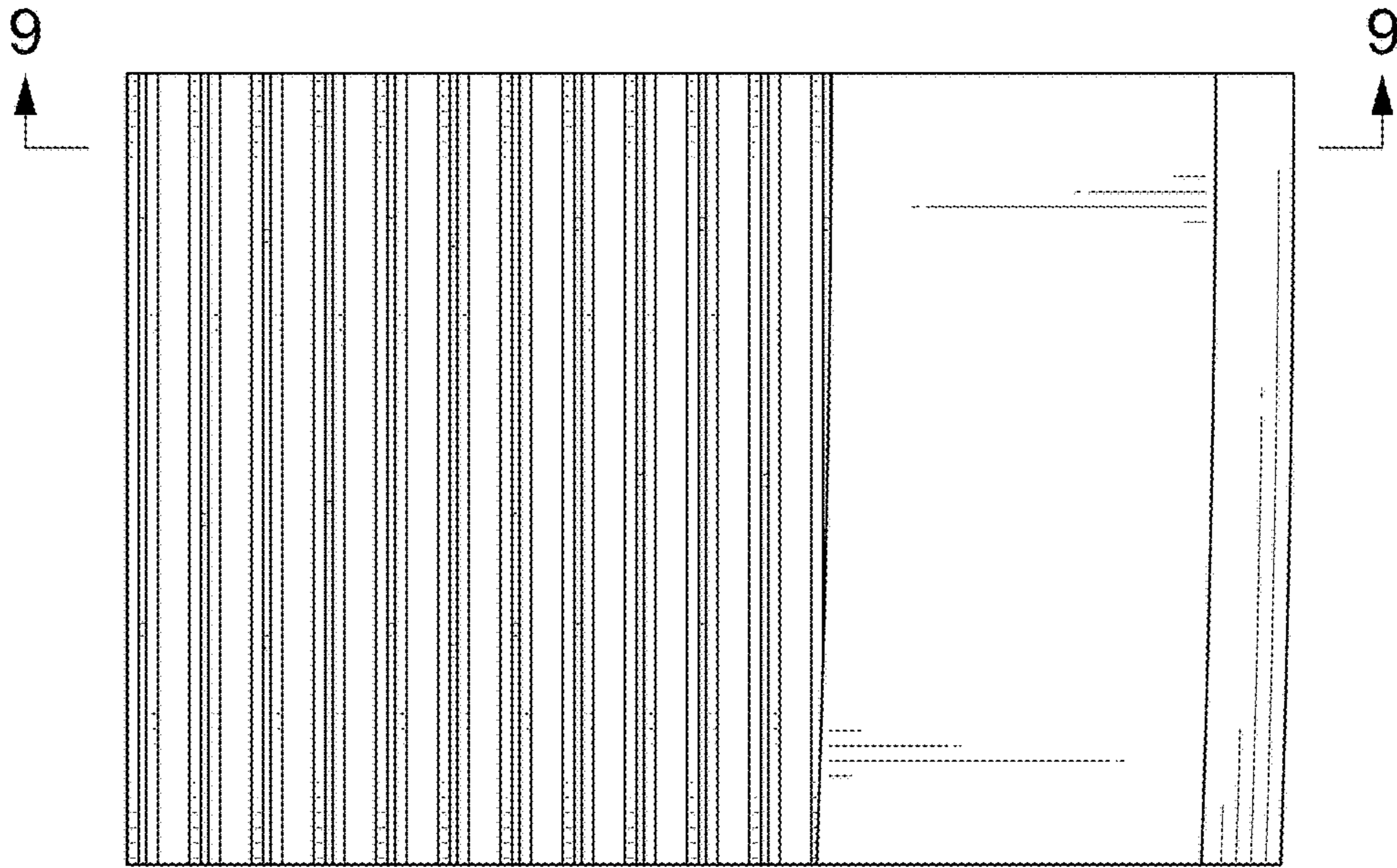


FIG. 7

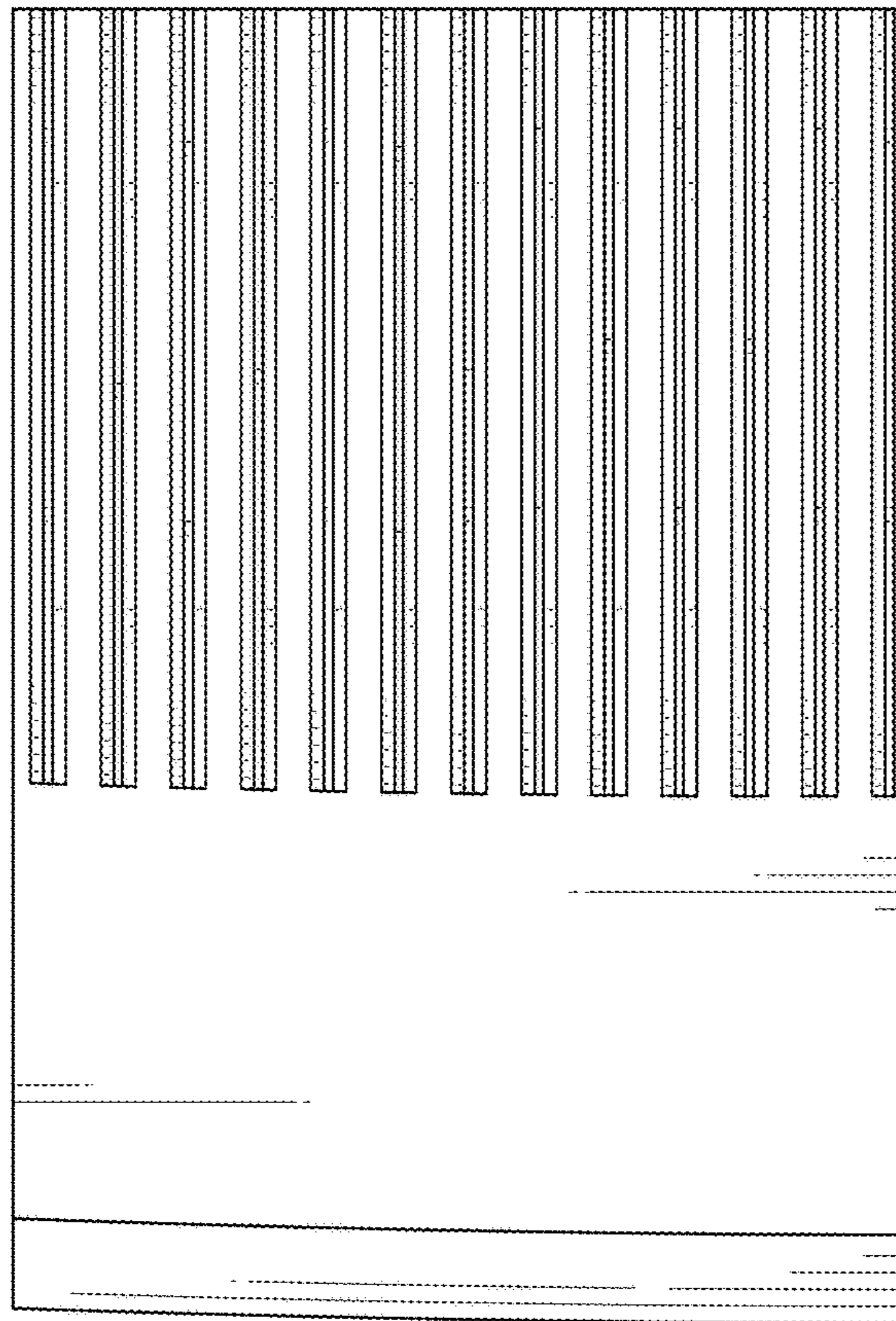


FIG. 8

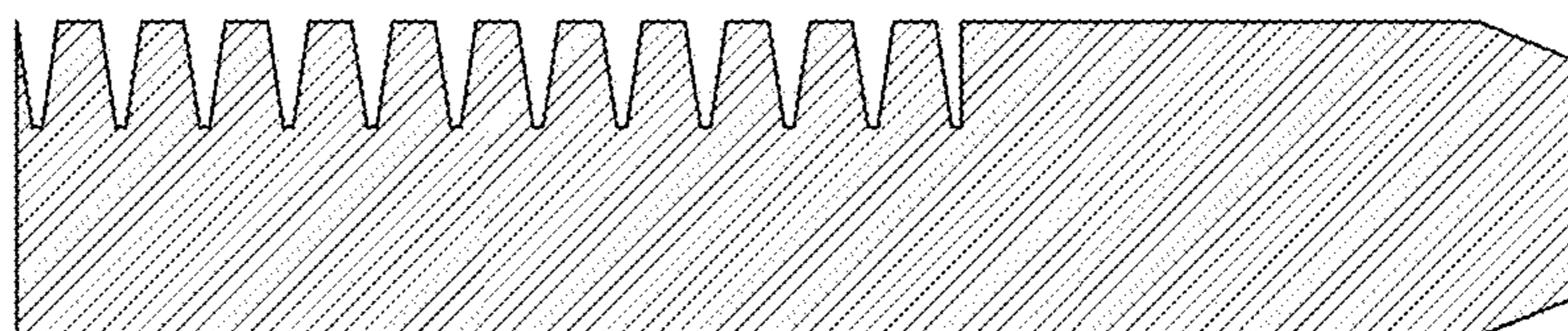


FIG. 9

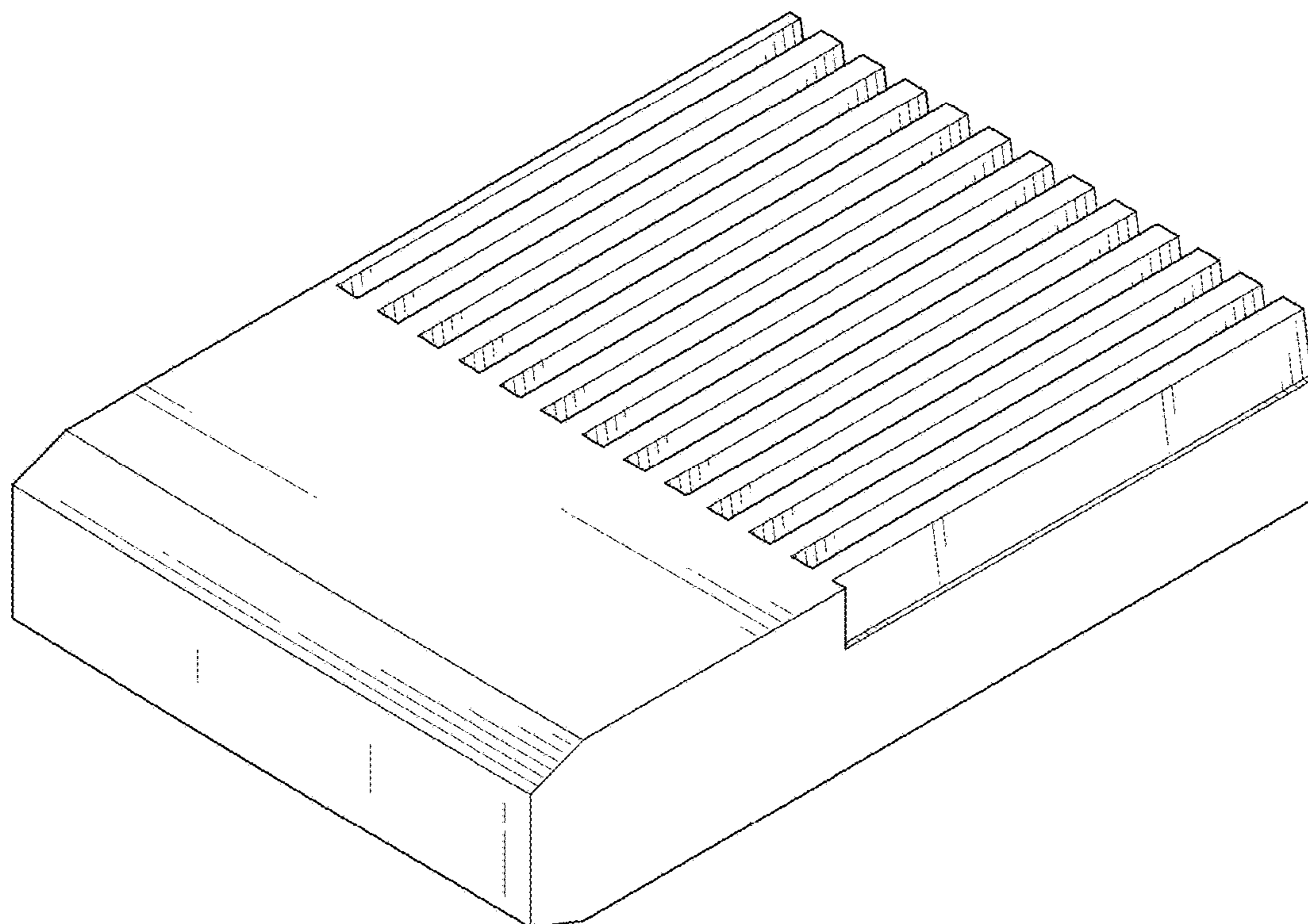


FIG. 10